

ABSTRACT

A lithography mask blank used as a material for producing a lithography mask includes at least one thin film which is formed on a substrate and has a
5 desired function. The blank has a nitrogen-containing thin film as the above-mentioned thin film and an ammonium ion production preventing layer for preventing production of ammonium ions, which is formed on the nitrogen-containing thin film or at least at a surface portion of the nitrogen-containing thin film and which is exposed on the surface of the lithography mask after the
10 lithography mask is manufactured.